

Amendments to the Claims

1. (CURRENTLY AMENDED) An apparatus for electrical measurement of an alignment of stitched masks, comprising:
 - a first test pad ~~101~~ and a second test pad ~~102~~ for measuring resistance therebetween;
 - a first resistive element ~~105,115~~ electrically connected at a first end to the first test pad ~~101~~ ;
 - a second resistive element ~~110,125~~ electrically connected at a first end to the second test pad ~~102~~;
 - said first resistive element ~~105,115~~ and said second resistive element ~~110,125~~ electrically connected by a vertical offset ~~112~~;
 - wherein the resistance measured between the first test pad ~~101~~ and the second test pad ~~102~~ is variable in accordance with an alignment of the first resistive element ~~105,115~~ and the second resistive element ~~110,125~~ relative to the vertical offset ~~112~~.
2. (CURRENTLY AMENDED) The apparatus according to claim 1, wherein the resistance measured between the first test pad ~~101~~ and the second test pad ~~102~~ decreases when the first resistive element ~~105,115~~ and the second resistive element ~~110,125~~ are misaligned in a first position.
3. (CURRENTLY AMENDED) The apparatus according to claim 1, wherein the resistance measured between the first test pad ~~101~~ and the second test pad ~~102~~ increases when the first resistive element ~~105,115~~ and the second resistive element ~~110,125~~ are misaligned in a second position, opposite to the first position.
4. (ORIGINAL) The apparatus according to claim 1, wherein when the first resistive element and the second resistive element are in substantial alignment, a resistance measurement of the resistive elements is approximately equal.
5. (ORIGINAL) The apparatus according to claim 1, wherein the first resistive element and the second resistive element are etched into respective masks that are superimposed to connect to each other.

6. (CURRENTLY AMENDED) The apparatus according to claim 1, wherein a second portion of the first resistive element ~~105, 115~~ and a second portion of the second resistive element ~~110, 125~~ at least partially overlap each other.
7. (CURRENTLY AMENDED) The apparatus according to claim 1, further comprising means for displaying ~~103~~ a resistance measured between the test pads.
8. (CURRENTLY AMENDED) The apparatus according to claim 1, further comprising sound means ~~103~~ that varies in pitch in accordance with a resistance measured between the pads.
9. (ORIGINAL) A method of electrically measuring an alignment of stitched masks, comprising the steps of:
 - (a) providing a first test pad and a second test pad for measuring resistance therebetween;
 - (b) electrically connecting a first resistive element to a first end of the first test pad;
 - (c) electrically connecting a second resistive element to a first end of the second test pad;
 - (d) connecting the first resistive element and the second resistive element together to opposite ends of a vertical offset; and
 - (e) measuring a resistance between the first test pad and the second test pad.
10. (ORIGINAL) The method according to claim 9, further comprising:
 - (f) determining whether the first resistive element and the second resistive element are in alignment by comparing the measured resistance with a predetermined resistance.
11. (ORIGINAL) The method according to claim 10, wherein an indicator means indicates whether a measured resistance is within a predetermined limit.

12. (ORIGINAL) The method according to claim 11, wherein the indicator means provides a visual indication.

13. (ORIGINAL) The method according to claim 11, wherein the indicator means provides an audiological indication.